Room Temperature Bonding of Sapphire with Sapphire or Metal Substrates in Air using Au Films

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1. Introduction

- ♦ Sapphire shows various attractive properties
 - High mechanical stress resistance (Young's modules)
 - High thermal conductivity
 - High chemical stability
 - Wide band transmittance property for optical light.
- Widely used as a wafer material for electronic or light devices, MEMS, watches, and so on.

Figure 1. sapphire substrates

Room temperature bonding using Au films in air [1,2] was applied for bonding sapphire–sapphire and sapphire–metal substrates.

<Purpose> To develop the potential applications of sapphire using room temperature bonding.



- [1] T. Shimatsu and M. Uomoto, ECS Trans., 33, 61 (2010)[2] H. Kon, M.uomoto and T. Shimatsu, WaferBond'13, P18, Srockholm (2013)
- Solution of the second second

Ti (5 nm) Sapphire (Al₂O₃) Mirror polished SUS or Al

Figure 3. film thickness

3. Bonding of sapphire and sapphire

♦ Sapphire substrates were bonded over the entire bonding area.



Sapphire plateSapphire ringBonded sampleFigure 4. Bonding samples

- Sapphire ring: φ32 mm-φ29.5 mm-2 mmt
 Sapphire plate: φ36 mm-1.2 mmt
 - Bonded area: 1.23 cm²
 - Loading pressure force: 10-50 MPa



<Structure (TEM cross-section images)>

• No vacancy was observed at the bonded interface.

<The bonding strength>

- Samples passed the 1 m height drop test using a metal case.
- No problems with water resistant test of 1 MPa.

4. Bonding of sapphire and mirror-polished metal

Bonding of sapphire and SUS was achieved.



 SUS ring φ24 mm-φ5 mm-4 mmt



<EELS spectrum> Comparing Ti layers on both sides to reference TiO_2 .

SUSSapphireBonded sampleFigure 6. Bonding samples (SUS and sapphire)

<TEM cross-section image>

- Images show that no interface corresponding to the original AI surfaces is visible; no vacancy is observed.
- ⇒ Recrystallization occurred at Au/Au bonded interface.

SF and HAADF images show that the interface between Ti underlayer and SUS is unclear compared to that on the other side.

- Sapphire plate
 - φ15 mm-6 mmt
- Bonded area: 1.57 cm²

A loading pressure force *F* of 10– 50 MPa was necessary for bonding (depending on the surface flatness of these substrates).

Figure 10. EELS

Ti layer on the SUS side shows a clear peek of O (Kα), and its spectrum is similar to that of reference TiO₂.

 \diamond Spectrum peek of Ti (L α) is

observed in both Ti layers.

Oxidization of the Ti layer on the SUS side is probably caused by the oxygen dissociated from the CrO_2 surface layer of SUS. Actually the free energy of formation of oxide compounds from Ti is smaller than that of Cr.

Bonding of sapphire and AI was also achieved.



Figure 11. Bonding sample (Al and sapphire)

Aluminum substrate
φ76 mm-8 mmt



Figure 12. Viewing port (bonded AI and sapphire)

 Bonding area of the Al flange φ70 mm- φ58 mm- 8 mmt

Sapphire Ti Au/Au Ti SUS

Figure 7. TEM cross-section image (BF)



Figure 8. TEM cross-section image (1) BF-STEM (2) HAADF-STEM

<EDX Elemental mapping> Measured elements: Ti, O, Au, Fe, Cr and Ni





Figure 9. elemental mapping

Ti is clearly observed on both side of Au/Au bonded films.

- Oxygen exists overlapping with Ti underlayers.
- ⇒ The Ti underlayer is likely to be oxidized.
- Sapphire substrate
 - φ76 mm-0.55 mmt
- Bonded area: 45.37 cm²

Sapphire substrate
φ70 mm-3 mmt
Bonded area: 12.06 cm²

5. Summary

Room temperature bonding of sapphire with sapphire and metals (SUS, AI) was achieved using Au films in air with reliable bonding strength.

The bonding technique can support expansion of the potential applications of sapphire in diverse industries.